

Title (en)

A CONCENTRATED CLEANING COMPOSITION

Title (de)

KONZENTRIERTE REINIGUNGSZUSAMMENSETZUNG

Title (fr)

COMPOSITION DE NETTOYAGE CONCENTRÉE

Publication

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Application

EP 22769213 A 20220825

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Abstract (en)

[origin: WO2023025884A1] The present invention is in the field of cleaning compositions. It relates to a concentrated liquid cleaning composition for forming a liquid detergent on dilution in water comprising: 10 to 50 wt% of an anionic surfactant selected from alkyl sulphate, alkyl ether sulphate, alkyl benzene sulphonate and combinations thereof; 1 to 10 wt% of an amphoteric surfactant; 1 to 20 wt% of a rhamnolipid; 1 to 10 wt% of a hydrotrope; and 0.1 to 15 wt% of a water-soluble inorganic salt, wherein the composition has a viscosity in the range 300 to 800 mPa.s and when diluted in water in 1:4 ratio by weight has a viscosity at least 1000 at 20 S-1 shear rate, 25°C, and wherein the pH of the composition is in the range from 4 to 7, wherein the ratio of rhamnolipid to hydrotrope is in the range from 1:1 to 6:1 by weight.

IPC 8 full level

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